

520.39737X00

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

Applicant(s):

T. OTSUBO

Serial No.:

09/842,000

Filed:

April 26, 2001

For:

PLASMA PROCESSING APPARATUS AND PROCESSING

**METHOD** 

Group:

1763

Examiner:

A. Crowell

## **AMENDMENT**

Commissioner for Patents Washington, D.C. 20231

March 20, 2003

CENT OF AMERICAN OF A TO THE CATO

Sir:

The following amendments and remarks are respectfully submitted in connection with the above-identified application in response to the Office Action dated December 20, 2002.

## IN THE SUBSTITUTE SPECIFICATION:

Page 27, please amend the paragraph beginning at line 8 as follows:

Radio frequency power is applied to the stage electrode 3 from the bias power supply 17 through transformer 29. Radio frequency current passes through the substrate 15 and the plasma, and flows to facing electrodes 2a and 2b. Since the transformer 29 is separated from or is floated with respect to the ground, almost all the radio frequency current flowing from the stage electrode 3 is fed to facing electrodes 2a and 2b, without going to any other places.

Page 28, please amend the paragraph beginning at line 13 as follows:

NE



Papers filed herewith on November 29, 2001    Fees \$		_503.39737x00 pril 26, 2001	UBO	Patent (2) Serial No09/842,000 Applicant(s)T. OTSU
Receipt is hereby acknowledged of the papers filed as indicated.		intsman of the state of the sta	Assignmer Letter to D Priority Do Petition for She E Specification &	☐ Fees \$ ☐ New Application ☐ Amendment Pre1. ☐ Notice of Appeal ☐ Appeal Brief ☐ Other _Substitute
THADEMARKS IN THADEMARKS		ract	pecification & Ab	Receipt is hereby acknowledged